



Molecular dynamics simulation of the full operation cycle of a HfO2-based RRAM cell

Laura Urquiza, Mahbub Islam, Adri van Duin, <u>Xavier Cartoixà</u> and Alejandro Strachan

UAB, Wayne State, Penn State, Purdue University

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Resistive switching (RS) phenomena

- RRAM devices store bits by switching memory cells between high resistance states (HRS) and low resistance states (LRS).
- The transition from HRS to LRS can be used to implement artificial synapses for neuromorphic computing or FPAAs.



Rainer Waser et. al., Adv. Mater. 2009, 21, 2632-2663

General mechanism of filamentary RS



- Electrochemical metallization memories (ECM): where the CF consists of metallic atoms injected from an active electrode into the dielectric.
- Valence change memories (VCM or OxRAM): associated to the valence change of the cations in the oxide produced by the clusterization of oxygen vacancies.

Experimental and theoretical evidence of filamentary conduction in OxRAM devices

 AFM three-dimensional reconstructed image of conductive channel in oxidebased resistive switching memory

Umberto Celano et. al., Nano Lett. 2015, 15, 7970-7975.



 Transport properties of oxygen vacancy filaments in metal/HfO₂/metal structures calculated with NEGF DFT

Cartoixà et. al. Phys. Rev. B, 86 (2012) 165445



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Molecular dynamics (MD) using EChemDID method allowed to simulate the

operation of ECM

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- EChemDID alters the electronegativities of the electrodes according to the supplied voltage: χ→χ ± φ/2
- Metallic atoms in contact with one electrode are given the corresponding χ alteration.
- Isolated metallic atoms or clusters contacting both electrodes are assigned a linear interpolation.



Onofrio et. al Nature Mater 14, (2015) 440-446.

How do we define an oxygen vacancy filament in VCM cells?

Conductive filament in **monoclinic HfO**₂



CF of Hf atoms bridging two oxygen vacancies (oxygen coordination = 5)



Coordination distribution in **amorphous HfO**₂



In our model, metallic Hf are described by Hf atoms with oxygen coordination ≤ 5 .

Hf/HfO2 interface relaxation



- **MD relaxation at 300 K and 1 atm** (allowing volume change along z).
- The time considered of 100 ps is long enough to ensure no more O atoms migrate towards active electrode.

Relaxation process

- The redox process induces an increase of oxygen vacancies in the oxide layer.
- Relaxation does not induce the formation of the conducting filament.
- From now on we only plot undercoordinated metal atoms. Lines connect atoms below a 3.9Å threshold.



Forming



Relatively low forming probability due to the small cross section of the simulated devices

Forming



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Forming dynamics



Electronegativity propagates dynamically as the conductive filament forms



Forming mechanism involves cascade of oxygen displacements towards AE



Filament stability at different applied bias



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Reset dynamics



Reset produced by oxygen diffusion in the xy plane



Oxygen diffusion during reset



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Set process



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Set dynamics



Set produced by oxygen diffusion in the xy plane, rather than vertical migration





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Take home messages

In amorphous oxides an oxygen vacancy should be thought of a proxy for an undercoordinated metallic atom.

 Strong indications that lateral diffusion is responsible for RESET and SET events.

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